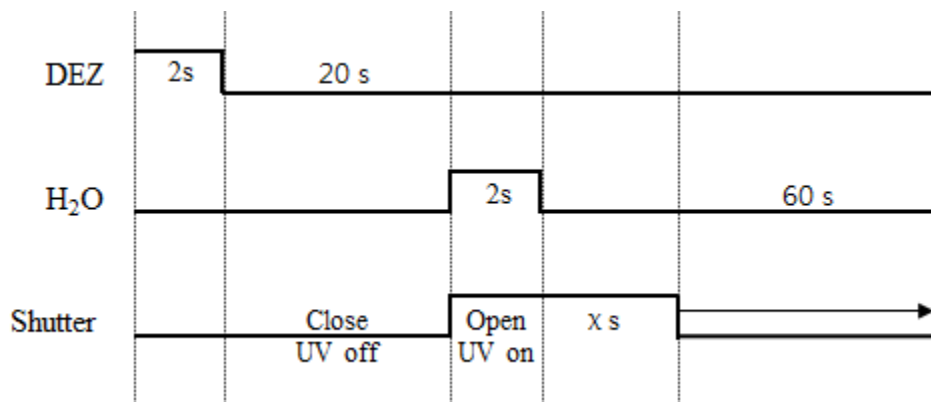


Electronic Supplementary Information (ESI)

Highly conductive air-stable ZnO thin film formation under in situ UV illumination for indium-free transparent electrode

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Scheme S1. A schematic representation showing ALD sequences used in growing ZnO film.

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[±] These authors contributed equally to this work.

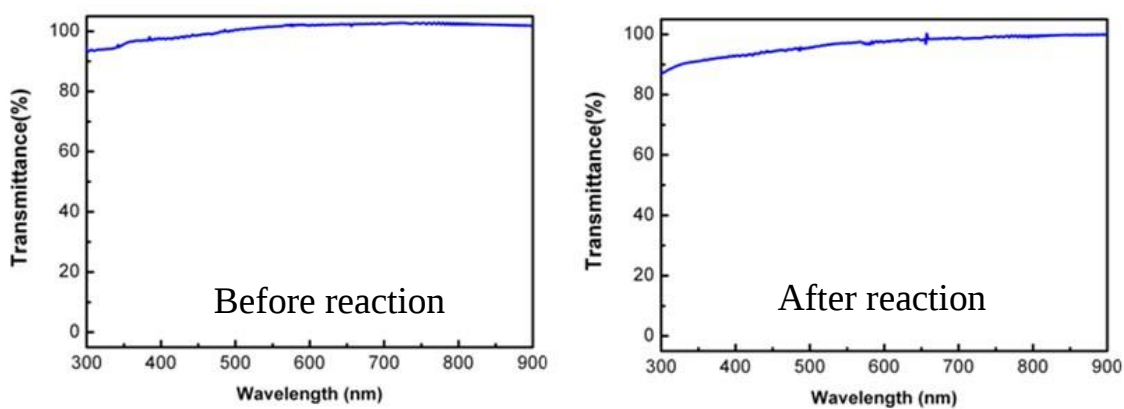


Fig. S1 Optical transmission spectra of CYTOP coat before and after ALD reaction for deposition of ZnO films.

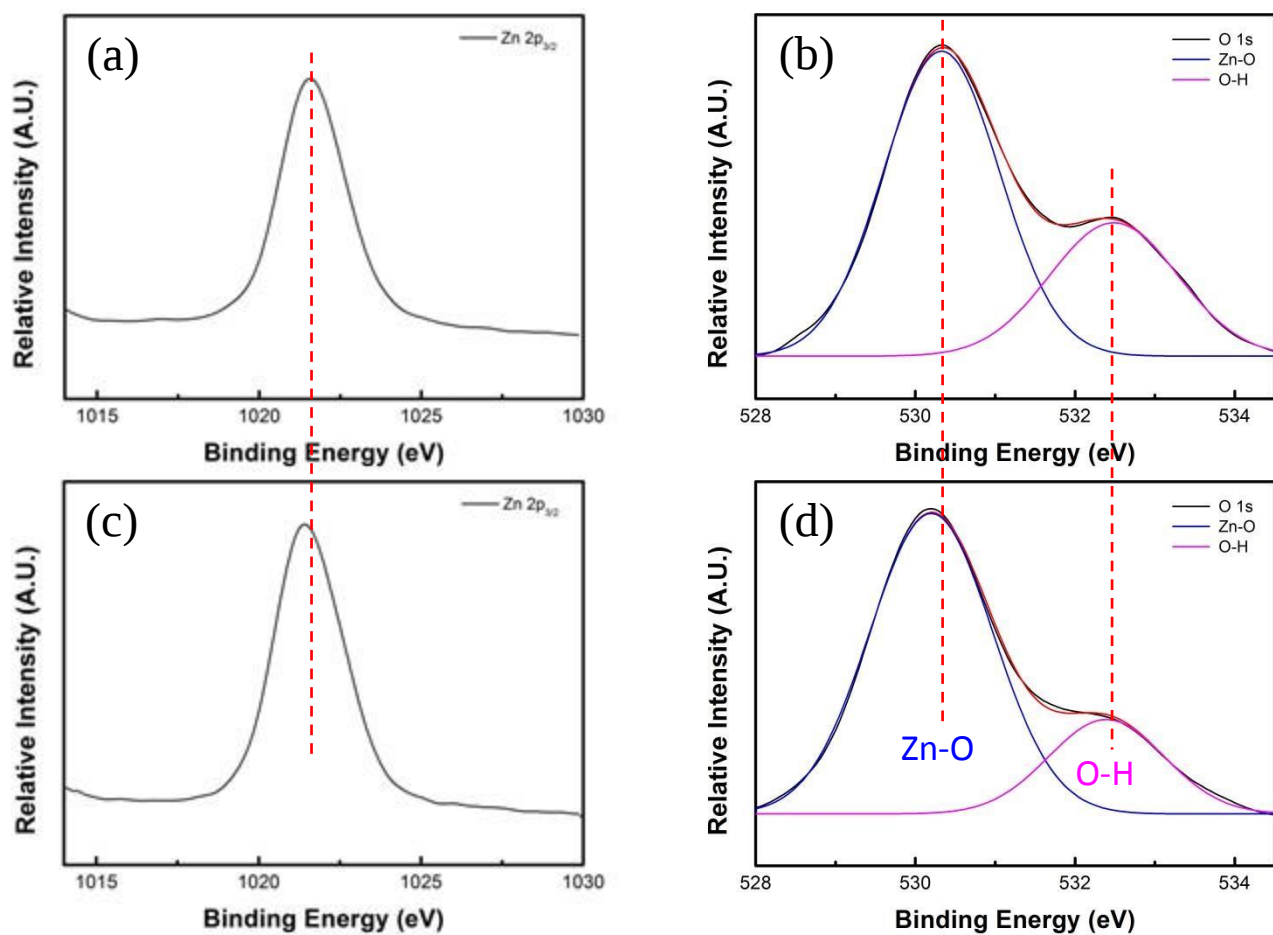


Fig. S2 Zn 2p_{3/2} and O 1s XPS spectra ZnO film. (a) and (b) pristine ZnO film without UV irradiation; (c) and (d) *in situ* UV irradiated ZnO film.